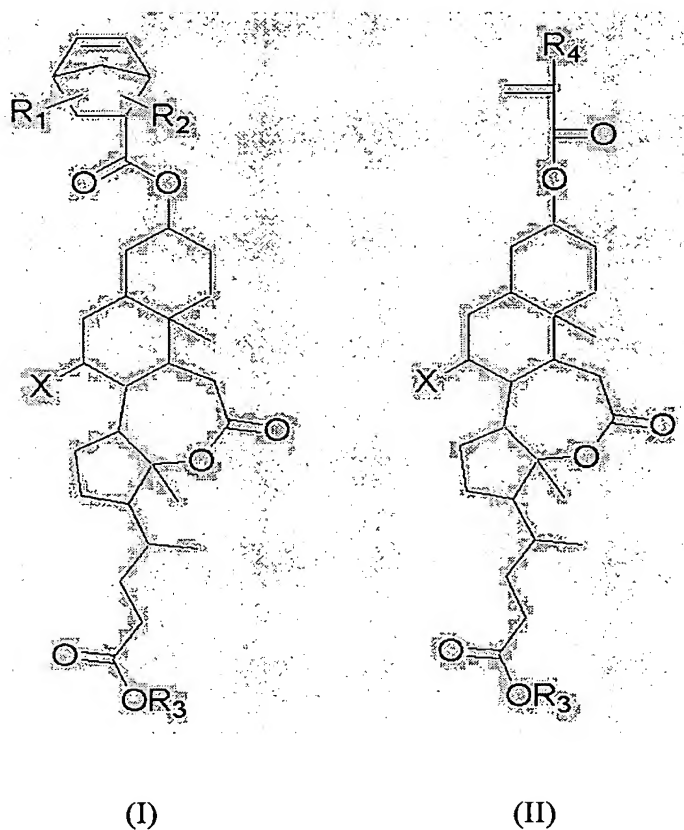


*Amendments to the Specification*

Please replace Paragraph [0024] with the following paragraph:

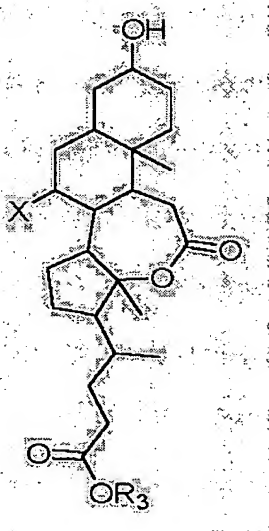
In the first embodiment of the present invention, norbornene, acrylate and methacrylate monomers containing an oxepan-2-one group, are represented by [[any]] one of Formulae (I) and (II):



wherein R<sub>1</sub>, R<sub>2</sub> and R<sub>4</sub> are each independently hydrogen, C<sub>1-4</sub> alkyl, C<sub>1-4</sub> alkoxy or phenyl; R<sub>3</sub> is hydrogen, C<sub>1-20</sub> alkyl, C<sub>1-20</sub> alkoxy, phenyl, C<sub>1-20</sub> hydroxyalkyl, C<sub>1-20</sub> alkoxyalkyl, C<sub>6-30</sub> alicyclic hydrocarbon or C<sub>6-30</sub> aliphatic lactone; and X is hydrogen or hydroxyl.

Please replace Paragraph [0025] with the following paragraph:

In the second embodiment of the present invention, a method for preparing the norbornene, acrylate and methacrylate monomers by reacting an alcoholic compound containing an oxepan-2-one group, which is represented by Formula (III):



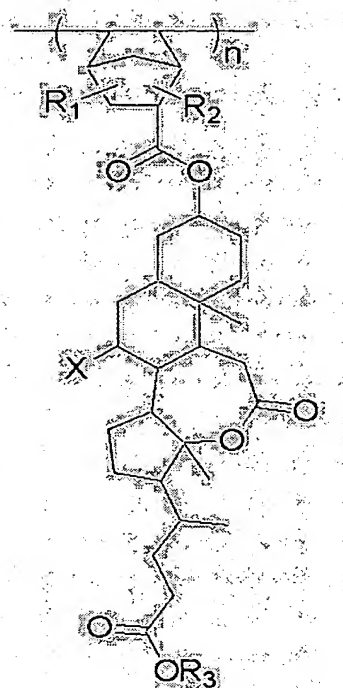
(III)

wherein  $R_3$  is hydrogen,  $C_{1-20}$  alkyl,  $C_{1-20}$  alkoxy, phenyl,  $C_{1-20}$  hydroxyalkyl,  $C_{1-20}$  alkoxyalkyl,  $C_{6-30}$  alicyclic hydrocarbon or  $C_{6-30}$  aliphatic; and X is hydrogen or hydroxyl, with 2-chlorocarbonyl-5-norbornene, acryloyl chloride or methacryloyl chloride at atmospheric pressure and  $0^\circ\text{C}$  for about one to about two hours, followed by reacting the reaction mixture at atmospheric pressure and room temperature for about 5 hours to about 6 hours.

Please replace Paragraph [0026] with the following paragraph:

In the third embodiment of the present invention, there is provided a photoresist composition, comprising:

a polymer represented by Formula (IV):



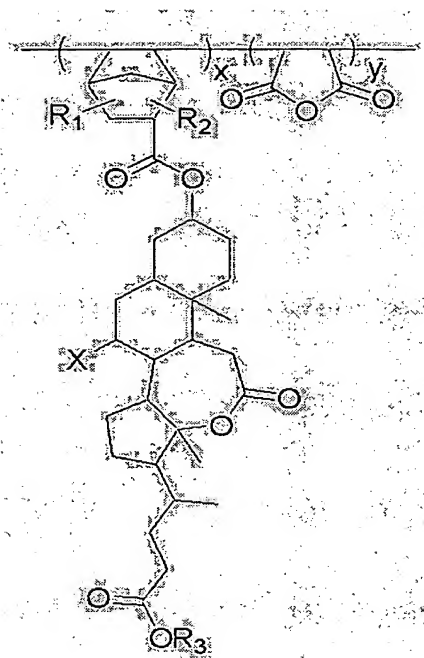
(IV)

wherein R<sub>1</sub> and R<sub>2</sub> are each independently hydrogen, C<sub>1-4</sub> alkyl, C<sub>1-4</sub> alkoxy or phenyl; R<sub>3</sub> is hydrogen, C<sub>1-20</sub> alkyl, C<sub>1-20</sub> alkoxy, phenyl, C<sub>1-20</sub> hydroxyalkyl, C<sub>1-20</sub> alkoxyalkyl, C<sub>6-30</sub> alicyclic hydrocarbon or C<sub>6-30</sub> aliphatic lactone; X is hydrogen or hydroxyl; and n represents the monomer or degree of polymerization and is an integer from about 1 to about 1000, and  
a photoacid generator.

Please replace Paragraph [0027] with the following paragraph:

In accordance with another aspect of the third embodiment of the present invention, there is provided a photoresist composition, comprising:

a polymer represented by Formula (V):



(V)

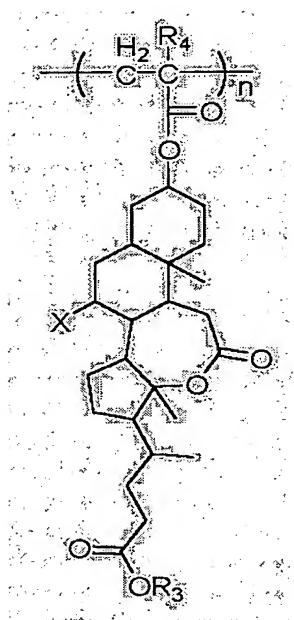
wherein  $R_1$  and  $R_2$  and  $R_4$  are each independently hydrogen,  $C_{1-4}$  alkyl,  $C_{1-4}$  alkoxy or phenyl;  $R_3$  is hydrogen,  $C_{1-20}$  alkyl,  $C_{1-20}$  alkoxy, phenyl,  $C_{1-20}$  hydroxyalkyl,  $C_{1-20}$  alkoxyalkyl,  $C_{6-30}$  alicyclic hydrocarbon or  $C_{6-30}$  aliphatic lactone; X is hydrogen or hydroxyl; and x and y each represents molar ratio of each monomer unit and the sum  $x + y$  is 1, and

a photoacid generator.

Please replace Paragraph [0028] with the following paragraph:

In accordance with another aspect of the third embodiment of the present invention, there is provided a photoresist composition, comprising:

a polymer represented by Formula (VI):



(VI)

wherein R<sub>1</sub>, R<sub>2</sub> and R<sub>4</sub> is [[are]] each independently hydrogen, C<sub>1-4</sub> alkyl, C<sub>1-4</sub> alkoxy or phenyl; R<sub>3</sub> is hydrogen, C<sub>1-20</sub> alkyl, C<sub>1-20</sub> alkoxy, phenyl, C<sub>1-20</sub> hydroxyalkyl, C<sub>1-20</sub> alkoxyalkyl, C<sub>6-30</sub> alicyclic hydrocarbon or C<sub>6-30</sub> aliphatic lactone; X is hydrogen or hydroxyl; and n represents the monomer or degree of polymerization and is an integer from about 1 to about 1000, and

a photoacid generator.

Please replace Paragraph [0033] with the following paragraph:

In accordance with another aspect of the fourth embodiment of the present invention, there is provided a method for preparing a photoresist composition, comprising:

homopolymerizing the ~~norbornene~~ monomer of Formula (II) or copolymerizing the monomer and maleic anhydride to prepare a polymer; and  
dissolving the polymer and a photoacid generator in a solvent.

Please replace Paragraph [0034] with the following paragraph:

In accordance with another aspect of the fourth embodiment of the present invention, there is provided a method for preparing a photoresist composition, comprising:

homopolymerizing the ~~norbornene~~ monomer of Formula (II), or copolymerizing the monomer and an acrylate or methacrylate monomer containing an alicyclic hydrocarbon or aliphatic lactone group, to prepare a polymer; and

dissolving the polymer and a photoacid generator in a solvent.